

Title (en)
APPARATUS FOR ELECTRON BEAM EVAPORATION

Title (de)
VORRICHTUNG ZUM ELEKTRONENSTRAHLVERDAMPFEN

Title (fr)
DISPOSITIF D'ÉVAPORATION SOUS FAISCEAU ÉLECTRONIQUE

Publication
EP 2038912 A1 20090325 (DE)

Application
EP 07764905 A 20070628

Priority
• EP 2007005715 W 20070628
• DE 102006031244 A 20060706

Abstract (en)
[origin: WO2008003425A1] The invention relates to an apparatus for electron beam evaporation, comprising a vacuum work chamber (2), a axial emitter (6) for generating an electron beam (7) by which a material (5) to be evaporated can be heated, and a diaphragm (9) disposed between the material (5) and a substrate (3) to be coated, the diaphragm being provided with at least one steam aperture (10) through which material vapor can flow to the substrate (3), wherein the diaphragm (9) comprises a magnetic system (14), by which the electron beam (7) can be deflected through the steam aperture (10) onto the material (5) to be evaporated.

IPC 8 full level
H01J 37/147 (2006.01); **H01J 37/305** (2006.01)

CPC (source: EP)
C23C 14/243 (2013.01); **C23C 14/30** (2013.01); **H01J 37/147** (2013.01); **H01J 37/3053** (2013.01); **H01J 2237/3137** (2013.01)

Citation (search report)
See references of WO 2008003425A1

Designated contracting state (EPC)
DE GB NL

Designated extension state (EPC)
AL BA HR MK RS

DOCDB simple family (publication)
DE 102006031244 A1 20080110; **DE 102006031244 B4 20101216**; CN 101484966 A 20090715; CN 101484966 B 20120530; EP 2038912 A1 20090325; JP 2009542900 A 20091203; JP 5150626 B2 20130220; WO 2008003425 A1 20080110

DOCDB simple family (application)
DE 102006031244 A 20060706; CN 200780025606 A 20070628; EP 07764905 A 20070628; EP 2007005715 W 20070628; JP 2009516988 A 20070628